

ABSTRACT

A method of processing a substrate, where the substrate is transferred from an ambient environment into a clean environment. The substrate is heated to at least a first temperature within the clean environment, and then maintained at no less than the first temperature within the clean environment. The substrate is selectively transferred within
5 the clean environment to more than one processing chambers, and processed in the more than one processing chambers. The substrate is transferred from the clean environment into the ambient environment.

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